

National Centre for Advanced Integrated Photonics (NCAIP) Technical Capabilities

Heterogeneous Integration	Si and III-V Fabrication at Nanyang Nano Fabrication Centre (N2FC) - Si fabrication: 150 mm and 200 mm wafers - III-V fabrication: 100 mm wafers and small dies Research and Technology Demonstrations Enabled by combined Si and III-V fabrication capabilities: - III-V quantum-cascade lasers, III-V multiple quantum well (MQW) devices, Heterojunction Bipolar Transistors, High Electron Mobility Transistors - Heterogeneous integration of III-V materials with silicon photonics - Metamaterials and topological materials Heterogeneous Integration Approaches - Monolithic integration of III-V materials on silicon - Heterogeneous integration via flip-chip bonding - Layer transfer and membrane technology - Strain-engineering techniques - Integration of emerging 2D materials, including hexagonal boron nitride (h-BN), and dichalcogenides (e.g. WSe₂, MoS₂)
	Flip-Chip Bonding - Chip size (upper die): 0.2 x 0.2 mm – 50 x 50 mm - Substrate size (lower die): 0.2 x 0.2 mm – 100 x 100 mm - Total thickness: 0.03 – 10 mm Bonding Arm - Alignment accuracy: ±0.1 µm - Post-bond accuracy: ±0.5 µm - Force: 1 – 1000 N Bonding Processes - Flip-chip bonding, Die bonding, Pick-and-place, Thermocompression, Thermosonic, Reflow, UV curing, Adhesive bonding, Sintering Materials - Gold, Gold/Tin, Indium, Copper, Adhesives



Silicon Photonics

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III-V Devices for Si-Photonics	Tunable Lasers* <i>*By end of FY2026</i>	- Max threshold current (I_{th}): 30 mA - Min power: 20 mW - Max linewidth: 10 kHz - Tuning range: 14 nm
	Frequency-Comb Lasers* <i>*By end of FY2027</i>	- Max threshold current (I_{th}): 30 mA - Min power: 20 mW - Max linewidth: 10 kHz - Tuning range: 14 nm - Multiwavelength: Up to 2 μm
	Communication-Band III-V Uni-Traveling Carrier (UTC) Photodetectors* <i>*By end of FY2026</i>	- Min InGaAs UTC bandwidth: 120 GHz - Min InGaAs UTC responsivity: 0.6 A/W
Quantum Photonic Devices and Platforms	Integrated Photon-Pair Source	- Peak spectral signal of ~24,000 detector counts from a single output arm at 3 mW off-chip pump power - Suitable for quantum communications and sensing
	Superconducting Nanowire Single-Photon Detector (SNSPD)	- Material: NbTiN - Can be fibre-coupled or waveguide-integrated - On-chip efficiency: 80% - Recovery time: 20 ns - Wavelength range: 500 nm – 3.7 μm - Optimised wavelength: 1.5 μm
Mid-Wave Infrared (MWIR) and THz Communications and Spectroscopy	Quantum Cascade Laser Source	- Single-mode and topological MWIR laser - Power: 5 mW
	Chip-to-Chip Bonding	- Ge/AlN on Sapphire or Si - Current yield: 70% (chip-on-chip)



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Mid-Wave Infrared (MWIR) and THz Communications and Spectroscopy	Demonstrated Devices	THz High-Bandwidth Wireless Data Communication - Waveguide Bandwidth: TE – 280 GHz, TM – 220 GHz Averaged TE/TM Bending Losses 90°, 0.3561 dB/turn 180°, 0.3882 dB/turn Averaged Path Losses - TE: 0.2190 dB/cm - TM: 0.1921 dB/cm THz Topological Waveguides - Waveguide Bandwidth 30 – 70 GHz - Propagation loss < 0.1 dB/cm 0 radius bends, bending loss < 0.1 dB Topological Antenna, Gain > 14 dBi - Leaky-wave Antenna (LWA) - Beam Steering Antenna THz Data Communication Platform (Wired/Wireless) - Aggregated data rates ~ 1 Tbps (wired) 3 – 6 wireless links, 72 Gbps single-link data rate
	Integrated Sensing Platforms for MWIR and THz	MWIR and THz Spectroscopy for Sensing* - MWIR band range: 3 – 14 μm on Si photonics platform - THz spectroscopy between 0.1 – 1 THz on Si photonics platform *By end of FY2031
Emerging Photonics Materials and Devices	Topological Electronic Materials	- Material synthesis: Molecular Beam Epitaxy - Material characterisation: In-situ Angle-Resolved Photoemission Spectroscopy (ARPES) and Scattering-type Scanning Near-field Optical Microscopy (S-SNOM)
	Polaritonic Waveguides in III-V Quantum Wells or Perovskite Films	- Propagation range: 100 – 300 μm π-phase shift: Within 10 μm - Modulation efficiency ($V\pi L$): 2 V·cm
	MEMS-Based Optical Switching* *By end of FY2026	Max switching speed: 600 ns

